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High radiation resistant crystals for X-ray and γ -radiation detectors

V. Sklyarchuk^a, P. Fochuk^a, Z. Zakharuk^a, A. E. Bolotnikov^b and R. B. James^{*c}

a – Chernivtsi National University, 2, Kotsiubynskoho Str., Chernivtsi, Ukraine, 58012
 b – Brookhaven National Laboratory, Upton, NY, USA, 11973
 c – Savannah River Laboratory, Aiken, SC, USA

ABSTRACT

Electrophysical properties of Hg₂MnInTe₆ single crystals grown by the modified zone melting method were studied. To expand the band-gap, a multiple part of Hg in 3(HgTe)-In₂Te₃ was replaced by an isovalent metal with a smaller ionic radius - Mn. Single crystals had n-type conductivity and possessed a resistivity of $\rho \approx 5 \times 10^6 \Omega \cdot \text{cm}$ (293 K), which was determined from the linear region of the current-voltage (*I-V*) characteristics for In/Hg₂MnInTe₆/In structure with two ohmic contacts. The product $\mu \tau \approx (1.7-3.4) \times 10^{-4} \text{ V}^{-1} \text{cm}^2$ is determined. Compensation degree (≈ 0.99) of the semiconductor material and the energy position of deep level $E_d \approx 0.37-0.4$ eV responsible for the dark conductivity were determined from measurements of the temperature dependence of the resistivity and space-charge limited currents (SCLC). From the optical measurements, the band-gap of single crystals was determined, which is equal to $E_g = 1.15 \text{ eV}$ (293 K). Au/Hg₂MnInTe₆/In structures with rectifying contacts were fabricated.

Keywords: radiation-resistant single crystals, Hg₂MnInTe₆, compensation degree, ohmic contact, Schottky contact, SCLC.

1.INTRODUCTION

Semiconductor crystals of $A_2^3 B_3^6$ group and their solid solutions are characterized by the high radiation resistance of electrical and

photoelectric parameters [1-3]. The widespread use of such semiconductors as ionizing radiation detectors is hindered by the low mobility of charge carriers, for example, for In_2Te_3 crystals, this value is less than $\mu \sim 10 \text{ cm}^2 V^{-1} \text{s}^{-1}$. Significantly better values of charge carrier mobility $\sim 500 \text{ cm}^2/(\text{Vs})$ were achieved for a solid solution of HgTe-In₂Te₃(composition 3:1). But the band-gap of 3(HgTe)-In₂Te₃ is relatively small (E_g = 0.72 eV). To expand the band-gap, a multiple part of Hg in 3(HgTe)-In₂Te₃ was replaced by an isovalent metal with a smaller ionic radius - Mn.

2.EXPERIMENTAL

Hg₂MnInTe₆ single crystals grown by the modified zone melting method had n-type conductivity and possessed a resistivity of $\rho \approx 5 \times 10^6 \ \Omega^*$ cm (293 K). The resistivity was determined from the linear section of the current-voltage (*I-V*) characteristics for a structure with two ohmic contacts. To create ohmic contacts, the Hg₂MnInTe₆ crystals of 4×4 mm² size and 0.8 mm thickness after appropriate mechanical grinding and polishing were chemically etched in 1% bromine-methanol solution and then rinsed in methanol. Ohmic contacts were obtained by thermal sputtering of indium after treatment of the crystal surface in an argon plasma. Thereafter, the structure was heated in vacuum at a temperature of T ≈ 445K for several seconds. A Schottky-type rectifying contact to the Hg₂MnInTe₆ structure was fabricated by applying a thin semi-transparent (~ 20 nm) layer of Au. The surface was treated in an argon plasma prior to the creation of the rectifying contact. An ohmic contact (In) was sputtered on the opposite side of the semiconductor wafer before the rectifying contact fabrication. The area of the ohmic contact was S ≈ 4 mm², and of the rectifying one – S ≈ 3-3.5 mm². Thus, Au/Hg₂MnInTe₆/In structures were obtained. Au/Hg₂MnInTe₆/In structures possessed a pronounced diode-like *I-V* characteristic. The initial section of *I-V* curves at reverse bias was well described in the framework of the Sah-Noyce-Shockley theory. At higher voltages, the *I-V* section, formed by the SCLC, is observed [4].

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3.RESULTS AND DISCUSSION



Fig. 1. *I-V* characteristics of Au/n-Hg₂MnInTe₆/In structure. Filled circles – direct bias, unfilled circles – reverse one. T = 300 K.

The small rectification coefficient is explained by the relatively large consistent resistance $R \approx (3-4) \times 10^6$ Ohm (293 K) of the crystal's neutral part. When illuminating the structure from the chromium-contact side by an incandescent lamp with a power of 20 W, an open-circuit voltage V $\approx (0.35-0.4)$ V was observed. The dependence of the differential resistance on the voltage is shown in Fig. 2.



Fig. 2. The photosensitivity spectra of Au/n-Hg₂MnInTe₆/In structure vs. the wavelength. Unfilled circles - without offset, filled circles - at reverse voltage V = 5 V.

The photosensitivity spectrum in the photovoltaic mode covers the range of wavelengths from 0.42 to 1.27 µm at $\lambda_{max} \approx 1.12$ µm. At the reverse bias V \approx 5 V, the photosensitivity spectrum expands to the wavelength range from 0.37 to 1.8 µm at $\lambda_{max} \approx 1.14$ µm. At reverse bias, the voltage is redistributed between the depleted layer of SCLC and the neutral part of the semiconductor, the resistance of which is R \approx (3-4)·10⁶ Ω at T = 293 K. Therefore, at V = 5 V we observe impurity photosensitivity for $\lambda_d \approx 1.56$ µm due to the resistive photo effect.

Fig. 3 shows the dependence of the differential resistance on the voltage.



Fig. 3. Dependence of differential resistance on voltage for the structure $Au-Hg_2MnInTe_6/In$. Filled circles - direct, unfilled - inverse offset (T=300 K). Inverse offset - "minus" on the Cr electrode. Crystal thickness was 0.74 mm.

As we see from Fig. 3, the differential resistance at a voltage at ≈ 100 V is approximately 10 times higher than the resistance of the neutral part of the crystal and is equal to $\rho \approx (7-8) \times 10^7 \Omega \times cm$. To determine the band-gap, we used the method described in [5,6]. Three plates of Hg₂MnInTe₆ single crystal with size 4x4 mm² and thickness d₁= 0.5 mm, d₂ = 0.25 mm and d₃ = 0.1 mm were prepared. For each plate from the optical transmission measurements, the width of the band gap E_g(d) of single crystals was determined.

$$\alpha_{\omega} \sim \left(\hbar\omega - E_g\right)^{1/2} \tag{1}$$

The value of $E_g(d)$ was determined by extrapolating the rectilinear sections of the dependences α_{ω} , built in the coordinates $\alpha_{\omega}^{-1/2} - \hbar \omega$, to the intersection with the energy axis $\hbar \omega$. The desired value of the band-gap Eg was determined according to $F = F_{\omega}(d) - \beta \log d$ (2)

where
$$E_g(d)$$
 is the experimental value of the band-gap for a sample of thickness d, and the coefficient β is found for each semiconductor from the slope of the line depicting the experimental dependence of $E_g(d)$ on $\lg d$ at T=const.

Expression (2) in semi-logarithmic coordinates is approximated by a line that cuts off on the abscissa at d=1 μ m, the desired value of the band-gap Eg = 1.15 eV (293 K).

As reported in [7], the definition of the product $\mu \cdot \tau$ is based on the use of the Hecht equation. Despite the general recognition of this technique, the assumption of a uniform electric field inside the detector is unjustified. This condition is not fulfilled in practice at relatively low voltages. As a result, it is necessary to measure at relatively high voltages, which leads to significantly lower values of the product $\mu \cdot \tau$ may proposed. From our point of view, such a method is technically difficult to implement in our case. Therefore, we used the method described in [8] to determine $\mu \cdot \tau$.

To determine the $\mu \cdot \tau$ product, the I–V curves of the In/Hg₂MnInTe₆/In structure with two ohmic contacts were used (293K). Voltage V_o is the voltage of the transition of the I–V section, where Ohm's law is fulfilled, to the currents limited by the SCLC. The voltage V_o was found as the point of intersection of the theoretical dependences I–V and I–V², respectively (Fig. 3). The product $\mu \cdot \tau$, according to [8], was determined

 $\mu \tau = d^2/V_o$ (3) where *d* is the thickness of the crystal (cm), V_o is the transition voltage of the I–V section, where Ohm's law I–V is valid to the quadratic I–V² dependence, which is formed by SCLC, is fulfilled (Fig. 4).



Fig. 4. Direct *I-V* characteristics for $In/n-Hg_2MnInTe_6/In:$ filled circles -T = 293 K, unfilled ones -T = 347 K. Crystal thickness was 0.74 mm.

For different single crystals, V_o was equal to $\approx 16-35$ V. Thus, from (3), $\mu\tau \approx (1.7-3.4) \times 10^{-4}$ V⁻¹cm² was obtained. To estimate the value of compensation degree of the grown $n-Hg_2MnInTe_6$ single crystals, the temperature dependence of their resistivity $\rho = \rho$ (T) was measured (Fig. 5).



The dependence $\rho = \rho$ (T) is equal to:

$$p = \frac{1}{q(n\mu_n + p\mu_p)},\tag{4}$$

From dependence (4) we define $\Delta \mu$:

$$\Delta\mu = E_g + kT \ln\left(\frac{1 + \sqrt{1 - 4q^2 \rho^2 \mu_n \mu_p N_v N_c \exp\left(-\frac{E_g}{kT}\right)}}{2q\rho\mu_n N_c}\right),\tag{5}$$

where n, p and μ_n, μ_p are the concentration and mobility of electrons and holes, respectively, N_d and N_a are the concentration of donors and acceptors, $N_c = 2(m_n k/2\pi\hbar)^{3/2}$ and $N_v = 2(m_p k/2\pi\hbar)^{3/2}$ are the densities of states in the respective bands, m_n, m_p are the effective masses of electrons and holes. The solution of the electroneutrality equation (6) was performed by the numerical method:

$$p + \frac{N_d}{1 + \exp\left(\frac{\Delta\mu - E_d}{kT}\right)} = n + \frac{N_a}{1 + \exp\left(\frac{E_a - \Delta\mu}{kT}\right)},\tag{6}$$

To do this, we used the temperature dependence of the band-gap $E_g(T)$, μ_n , and μ_p , which can be represented as: $E_{\mu}(T) = 1.27 - 4.2 \times 10^{-4} T$

h

$$E_{g}(T) = 1.27 - 4.2 \times 10^{4} T$$
(7)
$$\mu_{n} = 1.0 \times 10^{6} T^{-3/2}$$
(8)

$$= 1.0 \times 10 I \tag{8}$$

$$\mu_p = 4.4 \times 10^5 T^{-3/2} \tag{9}$$

The effective masses of electrons $m_{\rm p}$ and holes $m_{\rm p}$ are equal to $0.43m_{\rm o}$ and $0.35m_{\rm o}$ [9], respectively, where $m_{\rm o}$ is the mass of electron in vacuum. As shown in [10, 11], the electroneutrality equation has two solutions, which correspond to strong and weak compensation of the semiconductor material. You can choose the desired solution by measuring the temperature dependence of $V_0(T)$. If V_0 depends on the temperature, then we have a highly compensated material, if not, it is poorly compensated. Fig. 6 shows the temperature dependence of V_{o} (T).

Thus, from Figs. 3 and 6 we see that V_0 depends on temperature. It should be noted that the temperature dependence $\Delta \mu(T)$, found using the experimental temperature dependence $\rho(T)$, can be obtained only with a single combination of E_d and N_a/N_d . The coincidence of calculation and experiment was obtained at $E_d \sim 0.37$ -0.4 eV and $N_a/N_d \approx 0.99$.





4.CONCLUSIONS

The n-type Hg₂MnInTe₆ single crystals were grown by the modified zone melting method. From the measurements of the optical transmission of Hg₂MnInTe₆ single crystals, the band-gap $E_g = 1.15$ eV (293 K) was determined. From *I-V* measurements for In/*n*-Hg₂MnInTe₆/In structure with two ohmic contacts, the resistivity of single crystals $\rho \approx 5 \times 10^6$ Ohm-cm (293 K) was measured. The compensation degree (~0.99) of n-Hg₂MnInTe₆/In single crystal and the energy position of the deep level E_d (~ 0.37-0.4 eV), responsible for the dark conductivity, were determined. Complex studies of the temperature dependences of resistivity ρ and transition voltage V_0 from the *I-V* ohmic section to the SCLC, with the solution of an electroneutrality equation, were performed by a numerical method. Both structures with two ohmic contacts - In/*n*-Hg₂MnInTe₆/In and structures with a rectifying contact - Au/*n*-Hg₂MnInTe₆/In were fabricated. The product ($\mu \tau$)_n \approx (1.7-3.4)×10⁻⁴ V⁻¹cm² was determined. Hg₂MnInTe₆ semiconductor single crystals are characterized by a high radiation resistance of the electrical and photoelectric parameters, and they can be used both for the manufacture of radiation-resistant photodiodes in the optical range and for ionizing radiation detectors in the X- and gamma-ray energy range.

REFERENCES

[1] V. M. Koshkin, I. N. Volovichev, Yu. G. Gurevich, L. P. Gal'chinetskiy, I. M. Rarenko, Materials and devices with giant radiation resources. Kharkov, 2006.

[2] V. M. Koshkin, Yu. Dmitriev, Chemistry and Physics of Compounds with Loose Crystal Structure, Harwood Acad. Publishers. Ser. Chem. Rev., England – Switzerland, 1994. v. 2, part. 2, 138 p.

[3] I. Rarenko, D. Korbutyak, V. Koshkin, B. Danilchenko, L. Kosyachenko, P. Fochuk, V. Sklyarchuk, Z. Zakharuk, S. Dremlyuzhenko, A. Rarenko, Y. Nikonyuk, V. Kladko, L. Demchyna, S. Budzulyak, N. Vakhnyak, A. Medvid, E. Dauksta, Materials and photosensor devices with high radiation stability. Advanced Materials Research, 1117, p. 107-113 (2015).

[4] Sklyarchuk, V. M., Gnatyuk, V. A., Pecharapa, W., Low leakage current Ni/CdZnTe/In diodes for X/γ-ray detectors, Nucl. Instr. and Meth. in Phys. Res., A, A879, p. 101-105 (2018).

[5] Patent 108138. Ukraine. IPC HO1L 21/66. Method of determining the band gap of semiconductor materials / V. P. Makhniy, V. M. Sklyarchuk. - № u2015 11247; publ. 11.07.2016, Bull. №13.

[6] V. P. Makhniy, Yu. V. Vorobiev, V. M. Sklyarchuk, and J. González-Hernández. Improvement in optical band gap determination for cadmium telluride and related compounds // Telecommunications and Radio Engineering, 75(15), p. 1369-1376 (2016).

[7] A. E. Bolotnikov, G. S. Camarda, E. Chen, R. Gul, V. Dedic, G. DeGeronimo, J. Fried, A. Hossain, J. M. MacKenzie, L. Ocampo, P. Sellin, S. Taherion, E. Vernon, G. Yang, U. El-Hanany, and R. B. James, Use of the drift-time method to measure the electron lifetime in long-drift-length CdZnTe detectors // J. Appl. Phys. – 2016. – Vol. 120. – P. 104507; doi: 10.1063/1.4962540.

[8] V. M. Sklyarchuk, P. M. Fochuk. Patent № 87411, "Method for determining the charge transport parameters in semiinsulating materials based on CdTe and its solid solutions". 2014.

[9] G. G. Grushka, Z. M. Grushka, N. P. Gavaleshko. Ukrayins'kyy fizychnyy zhurnal, 30(2), p. 304 (1985).

[10] G. G. Roberts, F.W. Smidlin. Interpretation of Thermal Activation Energies in Wide Band-Gap Materials // Phys. Rev. 180, 785 (1969).

[11] A. V. Malovichko, S. V. Svechnikov, K. P. Shul'ga, Ukrayins'kyy fizychnyy zhurnal, 20(2) (1975).